

G20

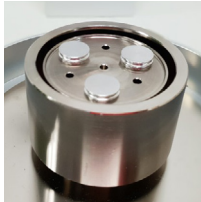
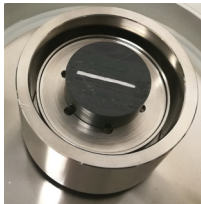
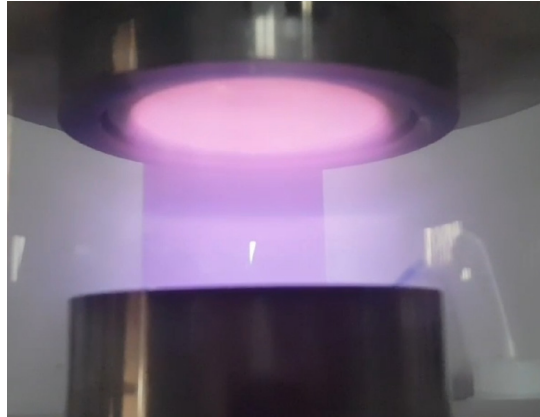
Powerful
high performance
Ion Sputter Coater



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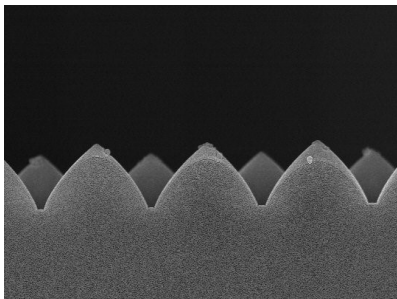
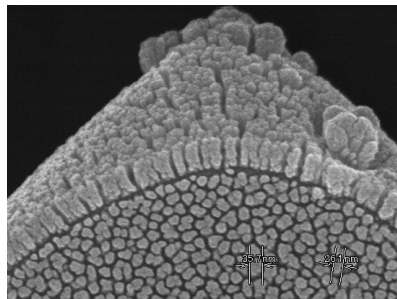
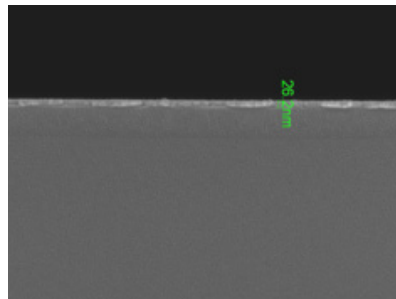
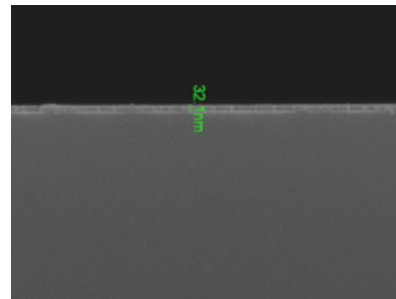
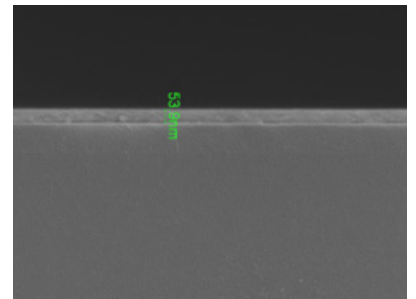
This equipment creates plasma on the surface of nonconductive and slightly conductive specimens to form metallic thin films and is a pre-treatment equipment that must be carried out when analyzing electron microscope(SEM). The target is mostly gold(Au) or platinum(Pt), and depending on the condition of the specimen, the thickness can be changed by adjusting the current and time

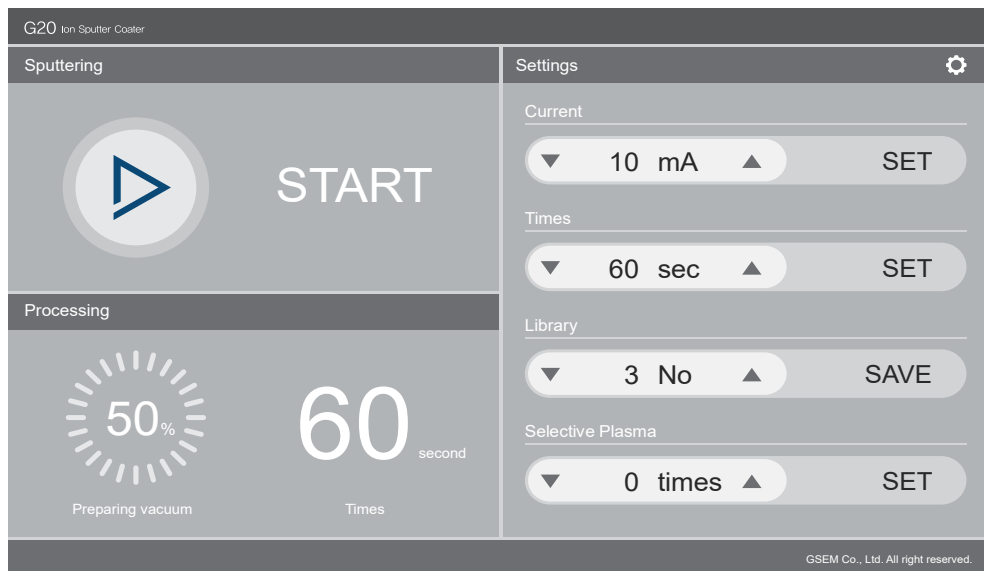
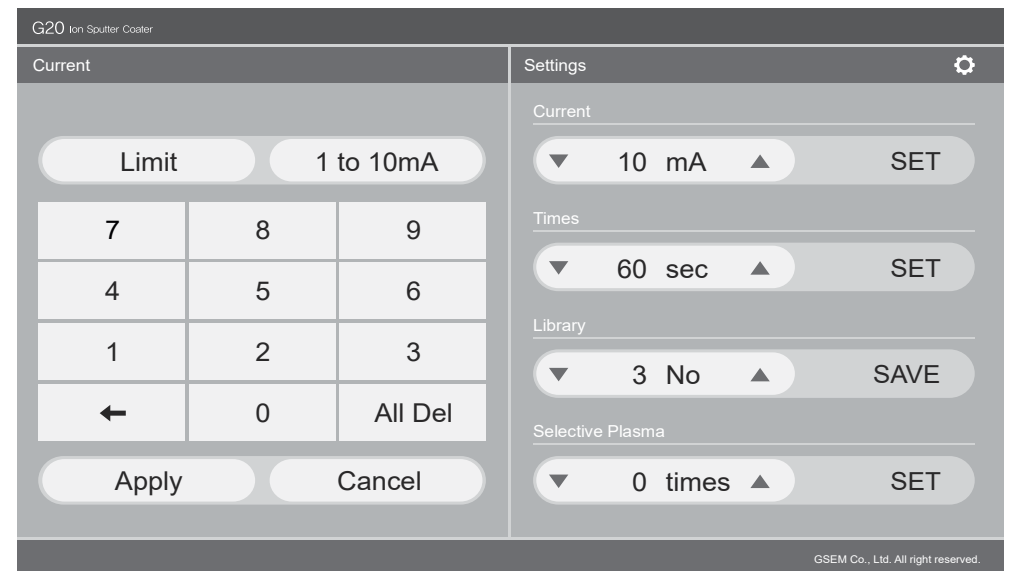


Major Features

- Easy Operation with 7" Touch Screen
- Vacuum-Auto Coating-Vent w/ One Touch Operation
- Parameter Saving with Library Function(Max.10)
- 7 Sample Stubs(Φ14mm) Together in Chamber
- Prevent damage to Specimens(Low Current:1~10mA)
- Minimize Footprint with Compact Product Size
- Very Good Uniformity with Pirani Gauge Inside

Coating Thickness





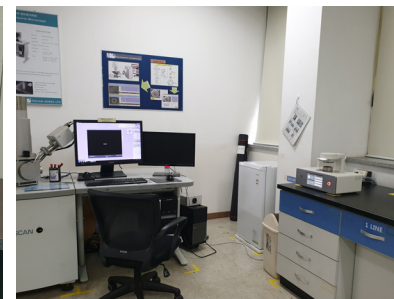
Directions

- Just touch start button then rotary pump starts running to create a vacuum.
- Plasma start to be generated by the entered time and current(Coating Thickness) when the set vacuum is reached
- When the coating is finished, the vacuum is automatically released and you can remove the sample by opening the door.

Functions

- Current : 1 to 10mA(1mA/Step)
- Time : 1 to 600sec(1sec/Step)
- Library : Max. 10 different coating condition
- Plasma : 0 to 9(Plasma on/off to minimize sample damage)

Installed View



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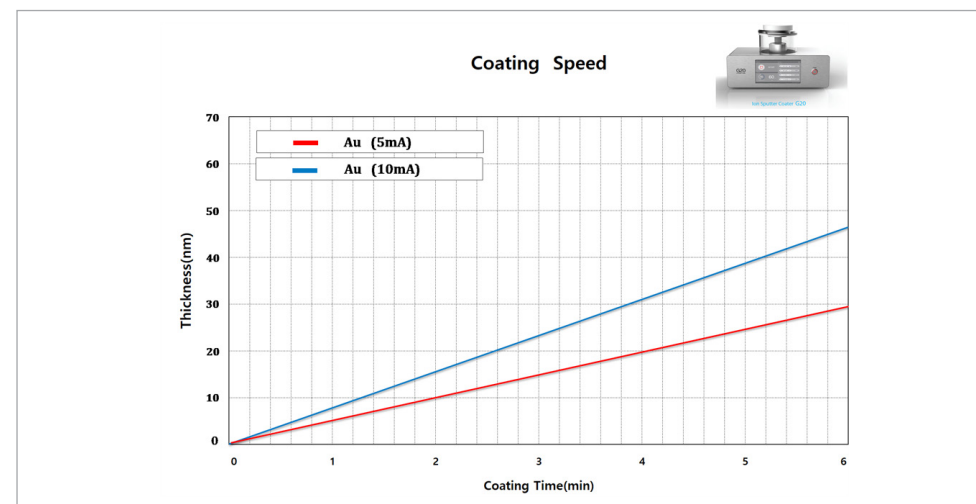
Specifications

Model	G20
Degree of Vacuum	2.0×10^{-1} Torr
Ion Current	1 to 10mA (1mA/step)
Target Material	Au or Pt
Chamber Size	Φ140mm(D) x 100mm(H)
Sample Stage	Φ50mm(D) x 25mm(H)
Target Size	Φ50mm(D)
Sputter Time	1 to 600sec (1sec/step)
Vacuum Pump	100L/min, Rotary Pump
Power	110~220VAC ±10%, 50/60Hz Single Phase. Max. 10A
Dimension	380(W) x 240(D) x 250(H)mm, 10kg

Applications

- Metal thin film coating on the surface of nonconductive and slightly conductive specimens
- Metal thin film deposition such as Au and Pt by sputtering deposition method
- Micro structure Analysis or Failure Analysis(Broken Sections)(Materials and products such as semiconductor parts, ceramics, metals, powder, etc)

Coating Speed (Thickness/Current/Time)



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